L Number	Hits	Search Text	DB	Time stamp
1	16	jp-2000159758-\$.did. jp-2002131917-\$.did.	USPAT;	2003/10/24 13:56
		jp-11305444-\$.did. jp-2001142213-\$.did.	US-PGPUB;	
		jp-2001188346-\$.did. jp-2001240625-\$.did.	EPO; JPO;	
		jp-2002116546-\$.did. jp-2002296783-\$.did.	DERWENT	
2	38	(US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or	USPAT;	2003/10/24 14:19
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	US-PGPUB;	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or	JPO	
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$).did. or		
		(US-20020009666-\$ or US-20010041303-\$ or		
		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
	•	US-20010033989-\$ or US-20010018162-\$ or		'
		US-20010010890-\$ or US-20010003640-\$).did. or		·
		(JP-2001142213-\$ or JP-2001188346-\$ or		
		JP-2001240625-\$).did.		
3	41	(((((((resin resist photoresist) and (acid near generat\$4))	USPAT;	2003/10/24 14:20
		and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4))) and (lactone)) and (((US-6403280-\$ or	EPO; JPO;	
İ		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
İ		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		,
		US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or		
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020058201-\$ or		
İ		US-20020051936-\$ or US-20020051935-\$ or		:
		US-20020048724-\$ or US-20020009668-\$ or		
İ		US-20020009667-\$ or US-20020004569-\$ or		
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or		
~		US-20010003640-\$).did.) ((((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))		

East Don't Remove

1	10	//////regin regist photogenist) and (acid many general #4))	USPAT;	2003/10/24 14:20
4	18	((((((((resin resist photoresist) and (acid near generat\$4))		2003/10/24 14:20
		and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4))) and (lactone)) and (((US-6403280-\$ or	EPO; JPO;	
]	US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
•		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or		
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020081525-\$ or		
		·		
		US-20020051936-\$ or US-20020051935-\$ or	* * *	
		US-20020048724-\$ or US-20020009668-\$ or		
		US-20020009667-\$ or US-20020004569-\$ or		
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or		
		US-20010003640-\$).did.) ((((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		,
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))) not		
		((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or		
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or		,
• •		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
	· ·	US-5929271-\$ or US-5910392-\$).did. or		
		(US-20020009666-\$ or US-20010041303-\$ or		
		US-20020009800-\$ of US-20020098441-\$ or		
				·
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		,
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
		US-20010010890-\$ or US-20010003640-\$).did. or		
	·	(JP-2001142213-\$ or JP-2001188346-\$ or	ľ	
		JP-2001240625-\$).did.)		
5	341	(resist photoresist) and (lactone) and ((maleic adj	USPAT;	2003/10/24 14:41
5	341			2003/10/24 14.41
		anhydride) (maleimide)) and (norbornene norbornyl)	US-PGPUB;	*
	1		EPO; JPO;	
			DERWENT	
6 .	17155	(acid photoacid) near generat\$4	USPAT;	2003/10/24 14:41
		- "	US-PGPUB;	1 .
			EPO; JPO;	
		•	DERWENT	
7	87099	positive near5 (composition working image pattern type)	USPAT;	2003/10/24 14:44
,	0,099	positive hears (composition working mage pattern type)	US-PGPUB;	
	1			
			EPO; JPO;	
			DERWENT	
8	4069	((acid photoacid) near generat\$4) and (positive near5	USPAT;	2003/10/24 14:45
		(composition working image pattern type))	US-PGPUB;	
			EPO; JPO;	
			Li O, ,, O,	

			•	
9	235	(((acid photoacid) near generat\$4) and (positive near5	USPAT;	2003/10/24 14:45
		(composition working image pattern type))) and ((resist	US-PGPUB;	,
		photoresist) and (lactone) and ((maleic adj anhydride)	EPO; JPO;	
		(maleimide)) and (norbornene norbornyl))	DERWENT	
10	202	((((acid photoacid) near generat\$4) and (positive near5	USPAT;	2003/10/24 14:45
		(composition working image pattern type))) and ((resist	US-PGPUB;	
İ		photoresist) and (lactone) and ((maleic adj anhydride)	EPO; JPO;	
		(maleimide)) and (norbornene norbornyl))) not	DERWENT	
ŀ		((jp-2000159758-\$.did. jp-2002131917-\$.did.		
		jp-11305444-\$.did. jp-2001142213-\$.did.		
		jp-2001188346-\$.did. jp-2001240625-\$.did.		
		jp-2002116546-\$.did. jp-2002296783-\$.did.)		
		((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or		
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or		
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		•		
		US-5929271-\$ or US-5910392-\$).did. or		
		(US-20020009666-\$ or US-20010041303-\$ or		
		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
		US-20010010890-\$ or US-20010003640-\$).did. or		
		(JP-2001142213-\$ or JP-2001188346-\$ or		
	*	JP-2001240625-\$).did.) (((((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		'
		alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and		
		(((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or		
		US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or		
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or		
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or		
		US-6448420-\$ or US-6280898-\$).did. or		
		(US-20010041303-\$ or US-20020009666-\$ or		
		US-20020132181-\$ or US-20020098441-\$ or		
	,	US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
		US-20010010890-\$ or US-20010003640-\$).did.) ((((((resin		
		resist photoresist) and (acid near generat\$4)) and (positive		
)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))		
		and (SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
	·	AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))))		
11	70187	nitrogen and surfactant	USPAT;	2003/10/24 14:47
		, in the second	US-PGPUB;	
			EPO; JPO;	
	I		DERWENT	

12	113	(nitrogen and surfactant) and (((((acid photoacid) near generat\$4) and (positive near5 (composition working image	USPAT; US-PGPUB;	2003/10/24 16:20
		pattern type))) and ((resist photoresist) and (lactone) and	EPO; JPO;	
		((maleic adj anhydride) (maleimide)) and (norbornene	DERWENT	
		norbornyl))) not ((jp-2000159758-\$.did.	DERVERY	
		jp-2002131917-\$.did. jp-11305444-\$.did.		
		jp-2002131917-3.did. jp-11303444-3.did.		
	•		•	
		jp-2001240625-\$.did. jp-2002116546-\$.did.		
		jp-2002296783-\$.did.) ((US-6448420-\$ or US-6280898-\$		
		or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or	00	·
	1	US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or		
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		,
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or		
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or		
		(US-20020009666-\$ or US-20010041303-\$ or		•
		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
·		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		
		US-20010033989-\$ or US-20010018162-\$ or		
		US-20010010890-\$ or US-20010003640-\$).did. or		,
		(JP-2001142213-\$ or JP-2001188346-\$ or		
		JP-2001240625- $\$$).did.) (((((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4))) and (lactone)) and		
		(((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or		
		US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or		
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		
•				
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or	·	
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or		
		US-6448420-\$ or US-6280898-\$).did. or		
		(US-20010041303-\$ or US-20020009666-\$ or		
		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		,
		US-20010033989-\$ or US-20010018162-\$ or		
•		US-20010010890-\$ or US-20010003640-\$).did.) ((((((resin		
		resist photoresist) and (acid near generat\$4)) and (positive		
)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))		
		and (SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))))))		
3	2	("6579659").PN.	USPAT;	2003/10/24 16:55
_	2	1 1000000000000000000000000000000000000	US-PGPUB;	
			EPO; JPO;	
			DERWENT	5
4		4570450 LIDDNI	USPAT	2003/10/24 14:20
4	0	6579659.URPN.	1	2003/10/24 16:20
.5	6	("5968713" "6013416" "6068512" "6200725"	USPAT	2003/10/24 16:21
,		"6280898" "6492091" "2001/0003640").PN.	LICDATE	0000/10/04 17 00
16	6706	(fluorine silicon) near5 surfactant	USPAT;	2003/10/24 17:09
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	

17	4693585	conventional improvement enhance enhancement improve	USPAT;	2003/10/24 16:57
17	4093363	benefit beneficial	US-PGPUB;	2003/10/24 10.37
		Schene Beneficial	EPO; JPO;	
			DERWENT	
18	930	((fluorine silicon) near5 surfactant) same (conventional)	USPAT;	2003/10/24 16:59
		improvement enhance enhancement improve benefit	US-PGPUB;	
		beneficial)	EPO; JPO;	
		·	DERWENT	
19	0	(((fluorine silicon) near5 surfactant) same (conventional	USPAT;	2003/10/24 17:00
		improvement enhance enhancement improve benefit	US-PGPUB;	
		beneficial)) and (positive near5 (composition working	EPO; JPO;	
		image pattern type)) and ((acid photoacid) near generat\$4)	DERWENT	
		and ((resist photoresist) and (lactone) and ((maleic adj		,
20	40	anhydride) (maleimide)) and (norbornene norbornyl))	LICDAT.	2002/10/24 17:10
20	49	(((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit	USPAT; US-PGPUB;	2003/10/24 17:10
		beneficial)) and (positive near5 (composition working	EPO; JPO;	
		image pattern type)) and ((acid photoacid) near generat\$4)	DERWENT	·
21	24	(((fluorine silicon) near5 surfactant) same (conventional	USPAT	2003/10/24 17:06
		improvement enhance enhancement improve benefit		2003/10/2117:00
		beneficial)) and (positive near5 (composition working		
		image pattern type)) and ((acid photoacid) near generat\$4)		
22	2	("4822713").PN.	USPAT;	2003/10/24 17:06
†			US-PGPUB;	
i			EPO; JPO;	
			DERWENT	
23	138	(fluorine-type silicon-type) near5 surfactant	USPAT;	2003/10/24 17:10
			US-PGPUB;	
-		·	EPO; JPO;	
24	1	((flyoning type cities type) mose 5 symfostout) and (nositive	DERWENT	2002/10/24 17:11
24	4	((fluorine-type silicon-type) near5 surfactant) and (positive near5 (composition working image pattern type)) and ((acid	USPAT; US-PGPUB;	2003/10/24 17:11
		photoacid) near generat\$4)	EPO; JPO;	
		photoacidy hear generatory	DERWENT	
26	13952	(((fluorine-type silicon-type) near5 surfactant) same	USPAT;	2003/10/24 17:11
		(conventional improvement enhance enhancement improve	US-PGPUB;	
		benefit beneficial)) amd (positive near5 (composition	EPO; JPO;	
		working image pattern type)) and ((acid photoacid) near	DERWENT	
		generat\$4)		
27	0	(((fluorine-type silicon-type) near5 surfactant) same	USPAT;	2003/10/24 17:12
		(conventional improvement enhance enhancement improve	US-PGPUB;	
		benefit beneficial)) and (positive near5 (composition	EPO; JPO;	
		working image pattern type)) and ((acid photoacid) near	DERWENT	
20	,	generat\$4)	LICDAT.	2002/10/24 17:12
28	1	((((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve	USPAT; US-PGPUB;	2003/10/24 17:12
		benefit beneficial)) and (positive near5 (composition	EPO; JPO;	
		working image pattern type))	DERWENT	
25	18	((fluorine-type silicon-type) near5 surfactant) same	USPAT;	2003/10/24 17:12
		(conventional improvement enhance enhancement improve	US-PGPUB;	
	1	benefit beneficial)	EPO; JPO;	
			DERWENT	
-	1863077	resin resist photoresist	USPAT;	2003/10/24 13:55
			US-PGPUB;	
		•	EPO; JPO;	·
			DERWENT	
-	8221	(resin resist photoresist) and (acid near generat\$4)	USPAT;	2002/10/10 12:17
			US-PGPUB;	
			EPO; JPO;	
	1		DERWENT	

		•		<u>.</u>
-	1522	"3" and (positive near composition)	USPAT; US-PGPUB;	2002/10/10 12:24
			EPO; JPO;	
	000	(4) 1 (4) 1 (4) 1	DERWENT	
-	203	((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/10 12:24
		(positive near composition)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	3892	((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/10 12:43
		(positive)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	("us-20010039080-A1.did.").PN.	USPAT;	2002/10/10 12:32
			US-PGPUB;	
	·		EPO; JPO;	
	1		DERWENT	
-	2	("20010039080").PN.	USPAT;	2002/10/10 12:32
			US-PGPUB;	
			EPO; JPO;	
1			DERWENT	
-	0	20010039080.URPN.	USPAT	2002/10/10 12:43
-	801	(((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/10 14:19
		(positive)) and (norborn\$5 alicyclic)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	288	((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/10/24 14:45
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)	EPO; JPO;	
		•	DERWENT	
-	721	SATO-KENICHIRO	USPAT;	2002/10/15 14:57
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	US-PGPUB;	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F	EPO; JPO;	
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F	DERWENT	
-	30	((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/04/29 09:41
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)) and (SATO-KENICHIRO	EPO; JPO;	
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	DERWENT	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
	250	AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)	LICDATE	0000/10/10 15 05
-	258	((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/10 16:06
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)) not ((((((resin resist photoresist) and (acid near	EPO; JPO;	
		generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and	DERWENT	
		(alkaline adj develop\$4)) and (SATO-KENICHIRO		
}		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		.
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F	1	
	70	AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))	TICDAT	2002/10/15 14:57
-	79	(((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT; US-PGPUB;	2002/10/13 14:37
•		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	EPO; JPO;	
		develop\$4)) not ((((((resin resist photoresist) and (acid near	DERWENT	
		generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and	DERWENT	
		(alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		·
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FOGI-PHOTO-F		
	289	((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/15 15:00
-	209	((((resin resist photoresist) and (acid near generat \$4)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	2002/10/13 13:00
		develop\$4)	EPO; JPO;	
		develop@4)	DERWENT	
	<u></u>		DERVICINI	

•	723	SATO-KENICHIRO	USPAT;	2002/10/15 15:01
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	US-PGPUB;	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F	EPO; JPO;	
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F	DERWENT	
-	259	(((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/15 15:01
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)) not (SATO-KENICHIRO	EPO; JPO;	
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	DERWENT	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)		
-	79	((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/15 15:01
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)) not ((((((resin resist photoresist) and (acid near	EPO; JPO;	
		generat\$4)) and (positive)) and (norborn\$5 alicyclic)) and	DERWENT	
		(alkaline adj develop\$4)) and (SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	•	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone)		
-	180	((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2002/10/15 16:11
		(positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4)) not (SATO-KENICHIRO	EPO; JPO;	
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	DERWENT	
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)) not (((((((resin		
		resist photoresist) and (acid near generat\$4)) and (positive		
)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))		
		not (((((((resin resist photoresist) and (acid near generat\$4))		
		and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj		
		develop\$4)) and (SATO-KENICHIRO		,
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone))		
	2	US-20010039080-\$.did.	USPAT:	2002/10/15 19:07
		,	US-PGPUB;	
		·	EPO; JPO;	
	1		DERWENT	
_	549	(resist photoresist) and (norborn\$5) and (\$5acid near	USPAT;	2002/10/16 11:41
	3.77	generat\$3)	US-PGPUB;	2002/10/10 11:11
		Series action	EPO; JPO;	
		·	DERWENT	
_	96	((resist photoresist) and (norborn\$5) and (\$5acid near	USPAT;	2002/10/16 11:44
	/5	generat\$3)) and((norborn\$5) same (conventional enhanc\$5	US-PGPUB;	2002/10/10 11:11
	,	improv\$5 benef\$3))	EPO; JPO;	
		p.2.40 believe011	DERWENT	
-	71	(((resist photoresist) and (norborn\$5) and (\$5acid near	USPAT;	2003/10/24 14:20
	'`	generat\$3)) and((norborn\$5) same (conventional enhanc\$5	US-PGPUB;	2000/10/24 14.20
•		improv\$5 benef\$3))) and positive	EPO; JPO;	
			DERWENT	
_	325	norbornene same (acrylate methacrylate) same (maleic adj	USPAT;	2002/10/16 11:54
-	323	anhydride)	US-PGPUB;	2002/10/10 11:35
		ainiyunue)	EPO; JPO;	
			DERWENT	
	7	"6294420"	E .	2002/10/16 14 50
-	7	"6284429"	USPAT;	2002/10/16 14:53
		· · ·	US-PGPUB;	
			EPO; JPO;	
		(II.CO.O.4.400II) PNA	DERWENT	000000000000000000000000000000000000000
•	2	("6284429").PN.	USPAT;	2002/10/16 14:53
			US-PGPUB;	
			EPO; JPO;	
	1	·	DERWENT	I

· T	35	(US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or	USPAT;	2003/04/29 09:39
·		US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or	US-PGPUB	
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or		
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or		
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or		
		US-6448420-\$ or US-6280898-\$).did. or		
		(US-20010041303-\$ or US-20020009666-\$ or		
ļ		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-2002009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		,
	:	US-20010033989-\$ or US-20010018162-\$ or		
		US-2001001390-\$ or US-20010003640-\$).did.		
	343	((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/04/29 09:43
	343	(((((resin resist photoresist) and (acid hear generative)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	2003/04/29 09.43
		develop\$4))	EPO; JPO;	
		αενειορφ4/)	DERWENT	
_	44	(((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/10/24 14:39
-	7-1-1	(((((resin resist photoresist) and (actit hear generation)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	2003/10/24 14.39
-		develop\$4)) and (SATO-KENICHIRO	EPO; JPO;	
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T	DERWENT	
}		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F	DERWENT	
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)		
	118	((((((resin resist photoresist) and (acid near generat\$4)) and	USPAT;	2003/04/29 09:44
-	110	((((((resir resist photoresist) and (acid near generation)) and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	2003/04/27 07:44
		develop\$4))) and (lactone)	EPO; JPO;	
*		develop\$4))) and (lactorie)	DERWENT	
	77	((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or	USPAT;	2003/04/29 09:44
-	//	US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or	US-PGPUB;	2003/04/27 07:44
		US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or	EPO; JPO;	
			DERWENT	
		US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or	DERWEINT	
		US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$).did. or		
		,		
		(US-20010041303-\$ or US-20020009666-\$ or		
İ		US-20020132181-\$ or US-20020098441-\$ or		
		US-20020081523-\$ or US-20020061465-\$ or		
		US-20020058201-\$ or US-20020051936-\$ or		
		US-20020051935-\$ or US-20020048724-\$ or		
		US-20020009668-\$ or US-20020009667-\$ or		
		US-20020004569-\$ or US-20010038969-\$ or		•
		US-20010033989-\$ or US-20010018162-\$ or	,	
		US-20010010890-\$ or US-20010003640-\$).did.) ((((((resin		
		resist photoresist) and (acid near generat\$4)) and (positive		
)) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4))		
		and (SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOȘHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))	ļ	1

	20	((((((//_scir_mosist_mbotomosist) and /scid_mos_mosist_04))	LICDAT	2002/10/24 14:10
-	38	((((((((resin resist photoresist) and (acid near generat\$4))	USPAT;	2003/10/24 14:19
		and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
·		develop\$4))) and (lactone)) and (((US-6403280-\$ or	EPO; JPO;	
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or		
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020058201-\$ or		
		US-20020051936-\$ or US-20020051935-\$ or		
		US-20020048724-\$ or US-20020009668-\$ or		_
		US-20020009667-\$ or US-20020004569-\$ or		
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or	·	
		US-20010003640-\$).did.) (((((resin resist photoresist) and		
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO		
				,
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		
· ·		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))	V I CD I T	2000/04/00 00
-	157	(((((((resin resist photoresist) and (acid near generat\$4))	USPAT;	2003/04/29 09:44
		and (positive)) and (norborn\$5 alicyclic)) and (alkaline adj	US-PGPUB;	
		develop\$4))) and (lactone)) (((US-6403280-\$ or	EPO; JPO;	
		US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or	DERWENT	
		US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or		
·		US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or		
		US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or		
		US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or		
		US-6280898-\$).did. or (US-20010041303-\$ or		
		US-20020009666-\$ or US-20020132181-\$ or		
		US-20020098441-\$ or US-20020081523-\$ or		
		US-20020061465-\$ or US-20020058201-\$ or		
		US-20020051936-\$ or US-20020051935-\$ or		
•		US-20020048724-\$ or US-20020009668-\$ or		
		US-20020009667-\$ or US-20020004569-\$ or		
		US-20010038969-\$ or US-20010033989-\$ or		
		US-20010018162-\$ or US-20010010890-\$ or		
		US-20010003640-\$).did.) (((((resin resist photoresist) and		,
		(acid near generat\$4)) and (positive)) and (norborn\$5		
		alicyclic)) and (alkaline adj develop\$4)) and		
		(SATO-KENICHIRO		
		SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T		
		AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F		•
		AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)))		